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Cu₂Si
ELETTRA

▼

10¹⁶ / cm²

100

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Cu₂Si
100

▼

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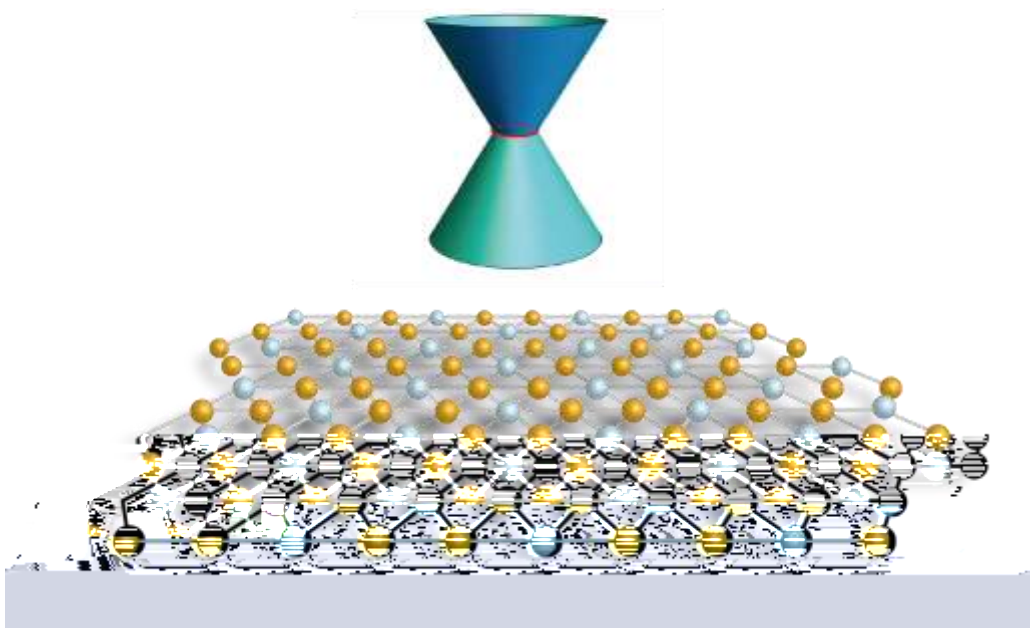
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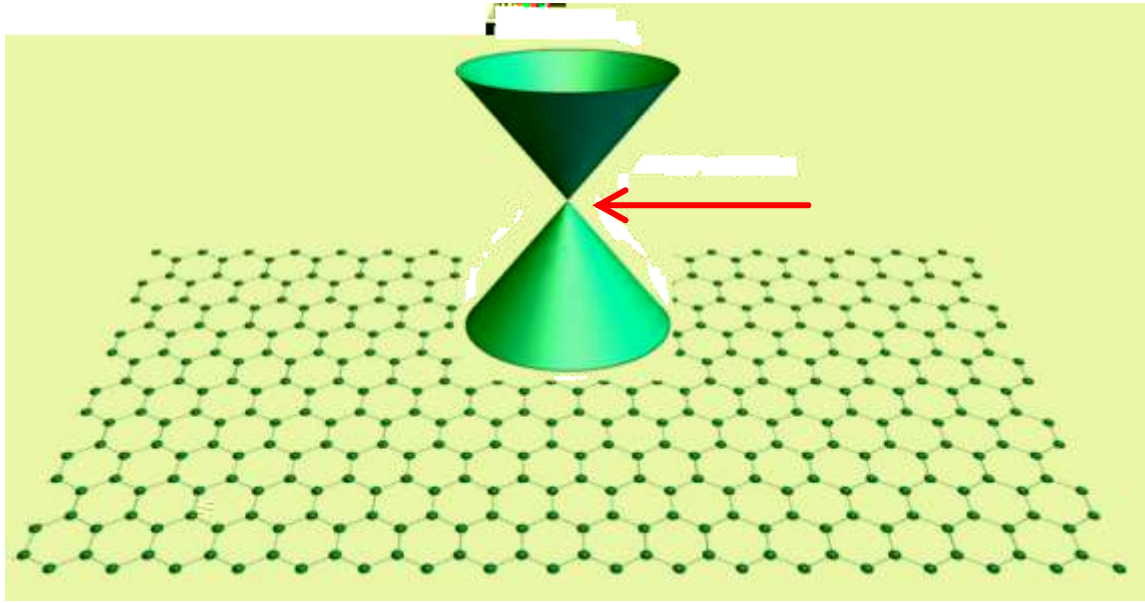
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Cu₂Si

Cu

Si



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